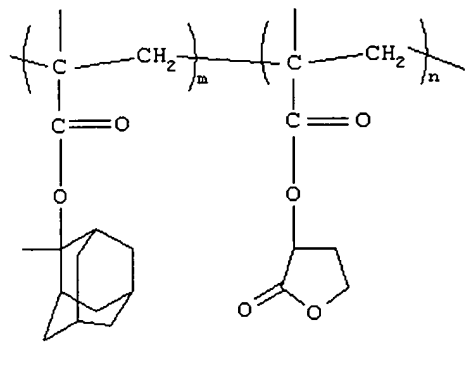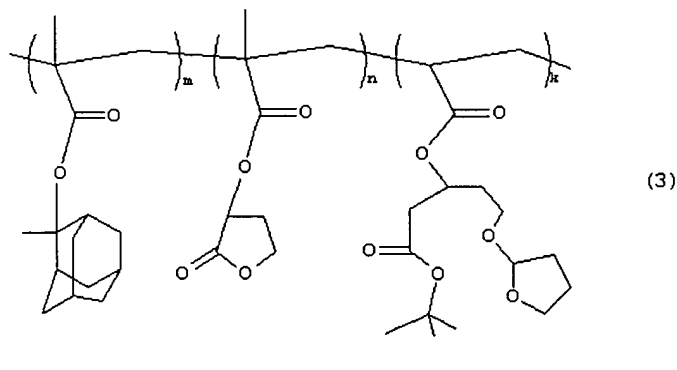## AMENDMENTS TO THE SPECIFICATION:

Please replace the formula beginning at page 3, line 20, with the following, rewritten

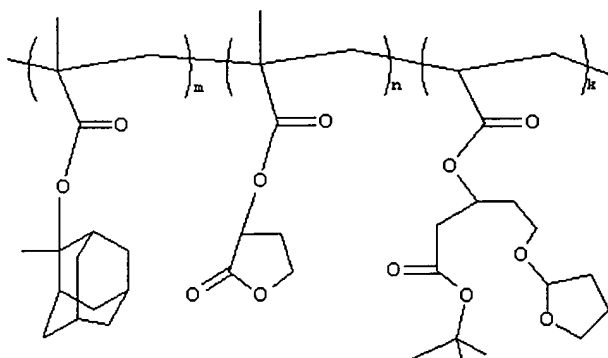formula:

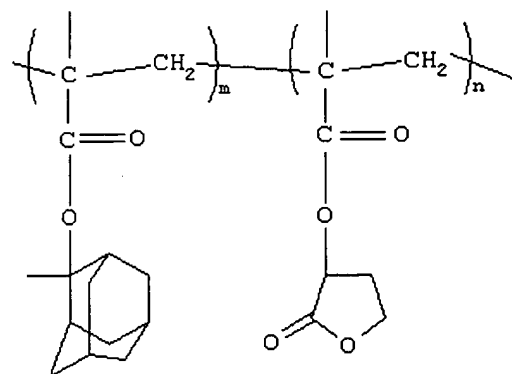**Please replace the formula beginning at page 9, line 17, with the following, rewritten**

formula:

(3)

Please replace the formula beginning at page 11, line 7, with the following, rewritten

formula:

Please replace the paragraph beginning at page 14, line 6, with the following, rewritten paragraph:
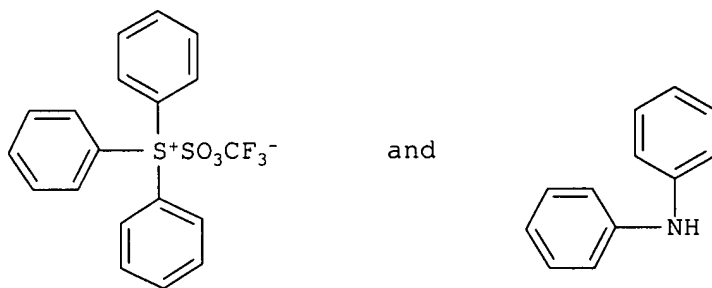
From two types of ~~metacrylic~~ methacrylic monomers, 2-methyladamantyl ~~metacrylate~~ methacrylate and gamma-butyrolactone methacrylate, a copolymer was prepared as described in JP-A-11-12326, the copolymer being represented by the formula:
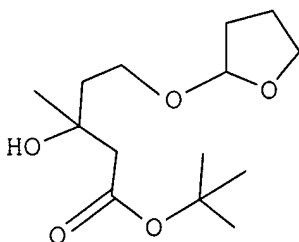

and having a weight average molecular weight of about 10,000 and an m/n ratio of 50:50. Using the copolymer as a base resin, a positive chemically amplified resist composition was prepared by

mixing 100 parts by mass of copolymer, 3 parts by mass of photo acid generator based on an onium salt of sulfonic acid and 0.2 part by mass of aniline-based quencher, the photo acid generator and the quencher being represented by the following formula, respectively:

The composition thus prepared was then dissolved in 1000 parts by mass of solvent (propylene glycol monomethyl ether acetate (PGMEA)), and two resist solutions were prepared by adding, to the resultant mixture, a compound represented by the formula:

as an additive, in amounts of 5% by mass and 10% by mass, based on the mass of the resist composition, respectively.

Please replace the formula beginning at page 17, line 1, with the following, rewritten

formula: